

PATENT APPLICATION

Sheet 1 of 1

FORM PTO-1449 LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)	ATTY. DOCKET NO. 10030753-1	SERIAL NO. 10/765.647
	APPLICANT Laura Wills Mirkarimi	
	FILING DATE Herewith	GROUP 1765

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	*	DOCUMENT NUMBER	DATE	NAME
ld		5,624,629	04/29/97	Randy J. Shul et al.
ld		5,338,394	08/16/94	Mohammed A. Fathimulla et al.

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	NAME	TRANSLATION	
					YES	NO

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, etc.)

ld	Chen, Hsin-Yi et al., "Inductively Coupled Plasma Etching of InP using CH ₄ /H ₂ and CH ₄ /H ₂ /N ₂ ", Journal of Vacuum Science Technology, B 20(1), Jan/Feb 2002, pp. 47-52.
ld	Hur, Katerina Y., et al., "Reactive Ion Etching of InP Via Holes", Journal of Vacuum Science Technology, B 12(3), May/Jun 1994, pp. 1410-1412.
ld	Feupier, Y. et al., "Influence of the Gas Mixture on the Reactive Ion Etching of InP in CH ₄ -H ₂ Plasmas, Journal of Vacuum Science Technology, B 15(5), Sep/Oct 1997, pp. 1733-1740.

EXAMINER ld	DATE CONSIDERED 9/12/05
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* Copies of these references are not enclosed pursuant to 37 CFR 1.98(d). (See accompanying IDS)

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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, etc.)

<div style="text-align: center; font-size: 1.5em;">80</div>		Grover, Rohit, "Process Development of Methane-Hydrogen-Argon-Based Deep Dry Etching of InP High Aspect-Ratio Structures with Vertical Facet-Quality Sidewalls", Journal of Vacuum Science Technology, B 19(5), Sept/Oct 2001, pp. 1694-1698.

EXAMINER <div style="text-align: center; font-size: 1.5em;">80</div>	DATE CONSIDERED <div style="text-align: center; font-size: 1.5em;">9/12/05</div>
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